



Low-temperature sintering of highly conductive ZnO:Ga:Cl ceramics by means of chemical vapor transport

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Abstract

A new technology for sintering a ZnO + Ga₂O₃ powder via chemical vapor transport based on HCl has been developed. The proposed sintering method has the following advantages: a low sintering temperature of 1000–1100 °C, there is no need to use of expensive dopant nanopowders, the possibility of multiple re-sintering, and the absence of changes in the diameter of the ceramics after sintering. A ZnO:Ga:Cl ceramics with a density of 5.31 g/cm³, a hardness of 2.0 GPa, and a resistivity of $1.46 \times 10^{-3} \Omega \cdot \text{cm}$ has been synthesized. The solubility limit of the Ga₂O₃ dopant has been estimated at about 3 mol %. At a higher doping level, the content of the ZnGa₂O₄ spinel phase becomes significant. In addition, ZnO:Ga:Cl thin films with a resistivity of $2.77 \times 10^{-4} \Omega \cdot \text{cm}$ can be grown by DC magnetron sputtering of the synthesized ceramics.